

Hypothetical BCT5 Si Structure:

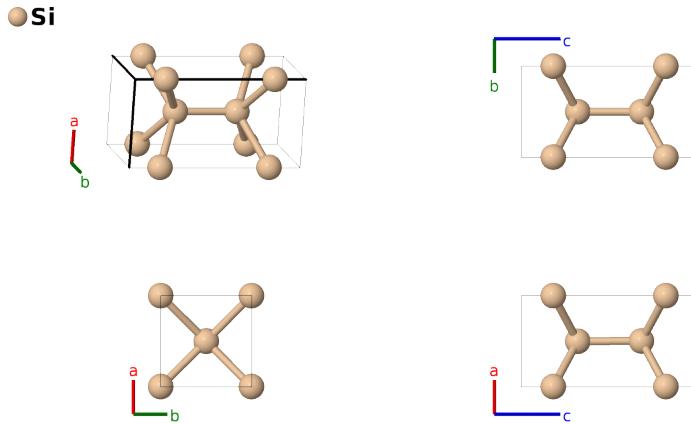
A_tI4_139_e-001

This structure originally had the label `A_tI4_139_e`. Calls to that address will be redirected here.

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<https://aflow.org/p/ZSDQ>

https://aflow.org/p/A_tI4_139_e-001



Prototype

Si

AFLOW prototype label

A_tI4_139_e-001

ICSD

none

Pearson symbol

tI4

Space group number

139

Space group symbol

$I4/mmm$

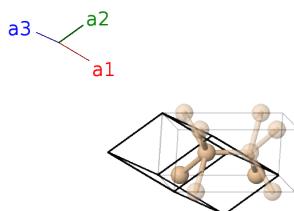
AFLOW prototype command

```
aflow --proto=A_tI4_139_e-001  
--params=a,c/a,z1
```

- The bct5 structure is a tetragonal analog of the diamond ($A4$) structure, with 5-fold coordination. It was proposed in (Boyer, 1991) as a low-energy metastable phase of silicon, based on first-principles calculations and model potentials. (Gerbig, 2012) found evidence of this structure in strained silicon.

Body-centered Tetragonal primitive vectors

$$\begin{aligned}\mathbf{a}_1 &= -\frac{1}{2}a\hat{\mathbf{x}} + \frac{1}{2}a\hat{\mathbf{y}} + \frac{1}{2}c\hat{\mathbf{z}} \\ \mathbf{a}_2 &= \frac{1}{2}a\hat{\mathbf{x}} - \frac{1}{2}a\hat{\mathbf{y}} + \frac{1}{2}c\hat{\mathbf{z}} \\ \mathbf{a}_3 &= \frac{1}{2}a\hat{\mathbf{x}} + \frac{1}{2}a\hat{\mathbf{y}} - \frac{1}{2}c\hat{\mathbf{z}}\end{aligned}$$



Basis vectors

	Lattice coordinates		Cartesian coordinates	Wyckoff position	Atom type
$\mathbf{B}_1 =$	$z_1 \mathbf{a}_1 + z_1 \mathbf{a}_2$	=	$cz_1 \hat{\mathbf{z}}$	(4e)	Si I
$\mathbf{B}_2 =$	$-z_1 \mathbf{a}_1 - z_1 \mathbf{a}_2$	=	$-cz_1 \hat{\mathbf{z}}$	(4e)	Si I

References

- [1] L. L. Boyer, E. Kaxiras, J. L. Feldman, J. Q. Broughton, and M. J. Mehl, *New low-energy crystal structure for silicon*, Phys. Rev. Lett. **67**, 715–718 (1991), doi:10.1103/PhysRevLett.67.715.
- [2] Y. B. Gerbig, C. A. Michaels, A. M. Forster, and R. F. Cook, *In situ observation of the indentation-induced phase transformation of silicon thin films*, Phys. Rev. B **85**, 104102 (2012), doi:10.1103/PhysRevB.85.104102.